

In the Abstract:

On Page 47, Line 2, after "filter", please insert -- not only --

On Page 47, Line 2, after "substances", please insert -- but also
for not generating hazardous contaminants --.

In the Claims:

Please ~~amend~~ the following claims.

In Claim 6, line 2, delete "or 5."

7. (Amended) A method for manufacturing a filter medium
for an air filter according to [any one of Claims 4 to 6] Claim 4 wherein said
polymer dispersion is obtained by first dissolving said hydrophilic monomer in
water, adding said hydrophobic monomer to this solution and dispersing said
hydrophobic monomer in said solution, and adding said polymerization
initiator to form a copolymer, and wherein volatile organic substances are
removed from said polymer dispersion by any one treatment of vacuum
suction, aeration, nitrogen purging, and steam injection.

A2
8. (Amended) An air filter comprising:
a filter medium according to [any one of Claims 1 to 3 or a
filter medium manufactured by a method according to any one of Claims 4 to
6] Claim 1; and
a frame and a sealing material incapable of generating
gaseous organic substances,
wherein said air filter is assembled in a space free of
gaseous organic substances.

In Claim 11, Line 2, after "trapping", insert -- at least one of --.

In Claim 11, Line 2, delete "and/or" and insert -- and --.

[Please add the following new claims:]

Sub
B3

1 12. (New) A method for manufacturing semiconductors, wherein
2 a silicon wafer for said semiconductor is processed in at least one of a clean
3 room and a local facility having an air filter as defined in Claim 8.

1 13. (New) A semiconductor device made by processing a silicon
wafer in at least one of a clean room and a local facility having an air filter as
defined in Claim 8.

Sub. E2
A3

1 14 (New) A local facility as defined in Claim 10 which
2 comprises a clean bench, a clean booth, a wafer stocker, wafer transfer space,
3 and semiconductor fabrication equipment.

1 15. (New) A local facility as defined in Claim 12 which
2 comprises a clean bench, a clean booth, a wafer stocker, wafer transfer space,
3 and semiconductor fabrication equipment

1 16. (New) A local facility as defined in Claim 13 which
2 comprises a clean bench, a clean booth, a wafer stocker, wafer transfer space,
3 and semiconductor fabrication equipment

1 17. (New) An air filter comprising:
2 a filter medium according to a filter medium manufactured by a
3 method according to Claim 4; and